

FIG. 1A
PRIOR ART

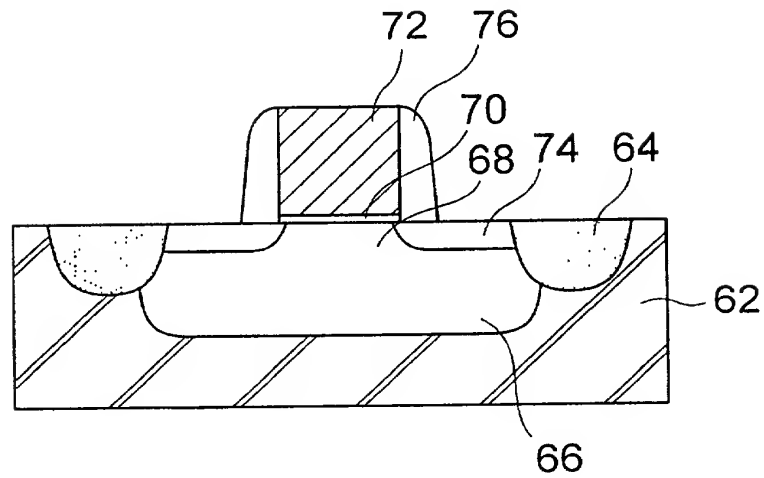


FIG. 1B
PRIOR ART

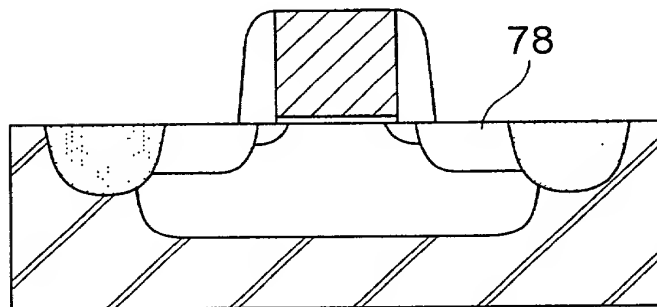


FIG. 2

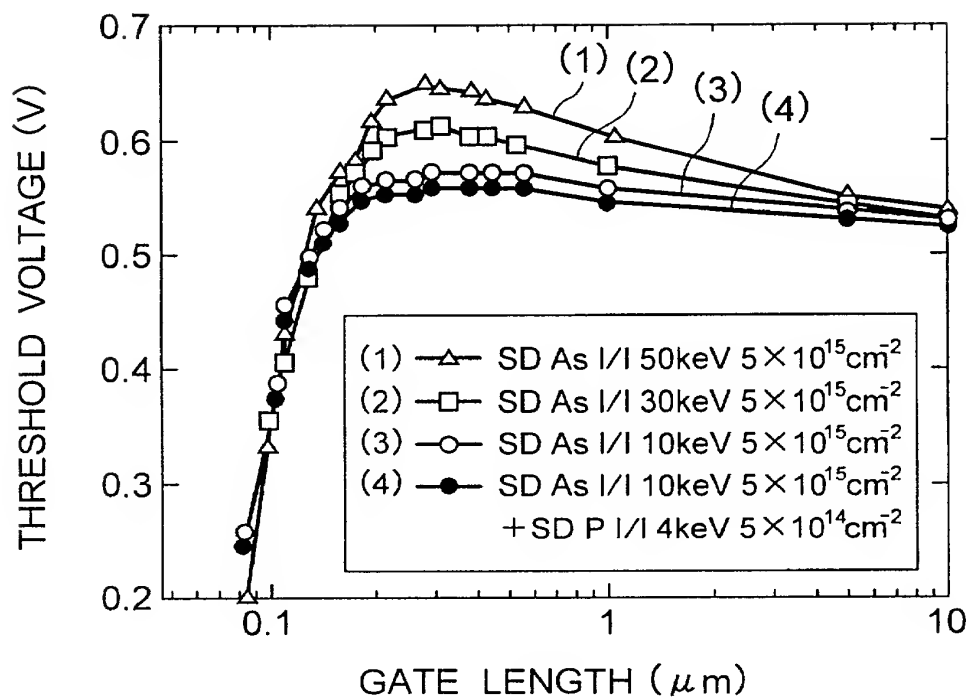


FIG. 3

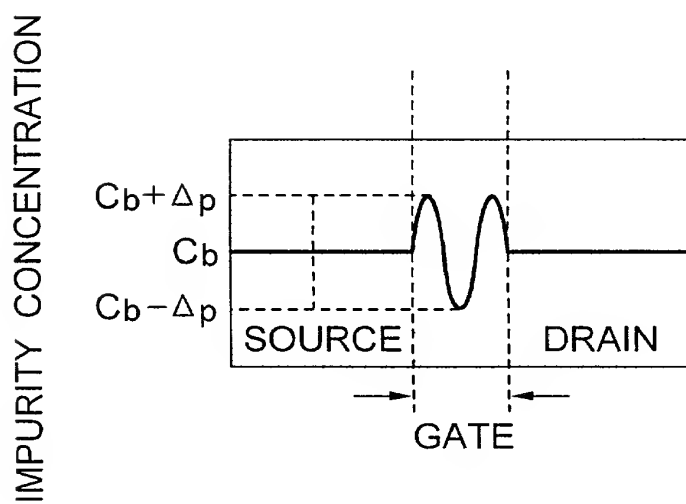


FIG. 4

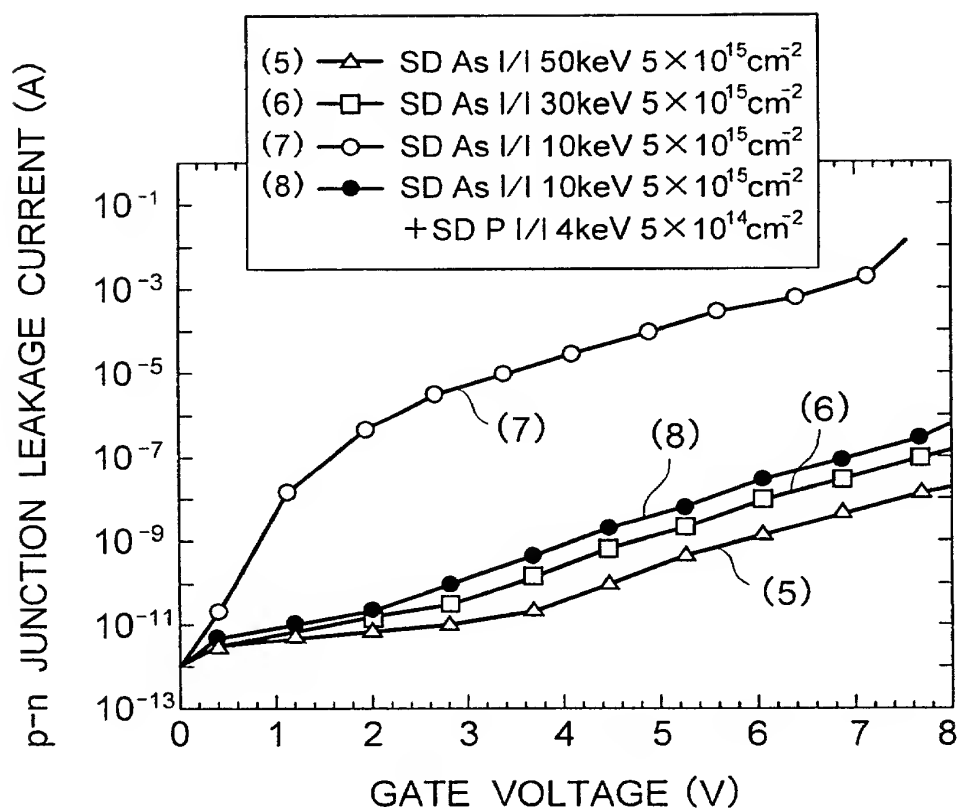


FIG. 5

INTERFACE BETWEEN AMORPHOUS SILICON
REGION AND SILICON MONOCRYSTALLINE
REGION WHEN As IS IMPLANTED AT
10keV AND $5 \times 10^{15} \text{cm}^{-2}$

INTERFACE BETWEEN AMORPHOUS SILICON
REGION AND SILICON MONOCRYSTALLINE
REGION WHEN As IS IMPLANTED AT
50keV AND $5 \times 10^{15} \text{cm}^{-2}$

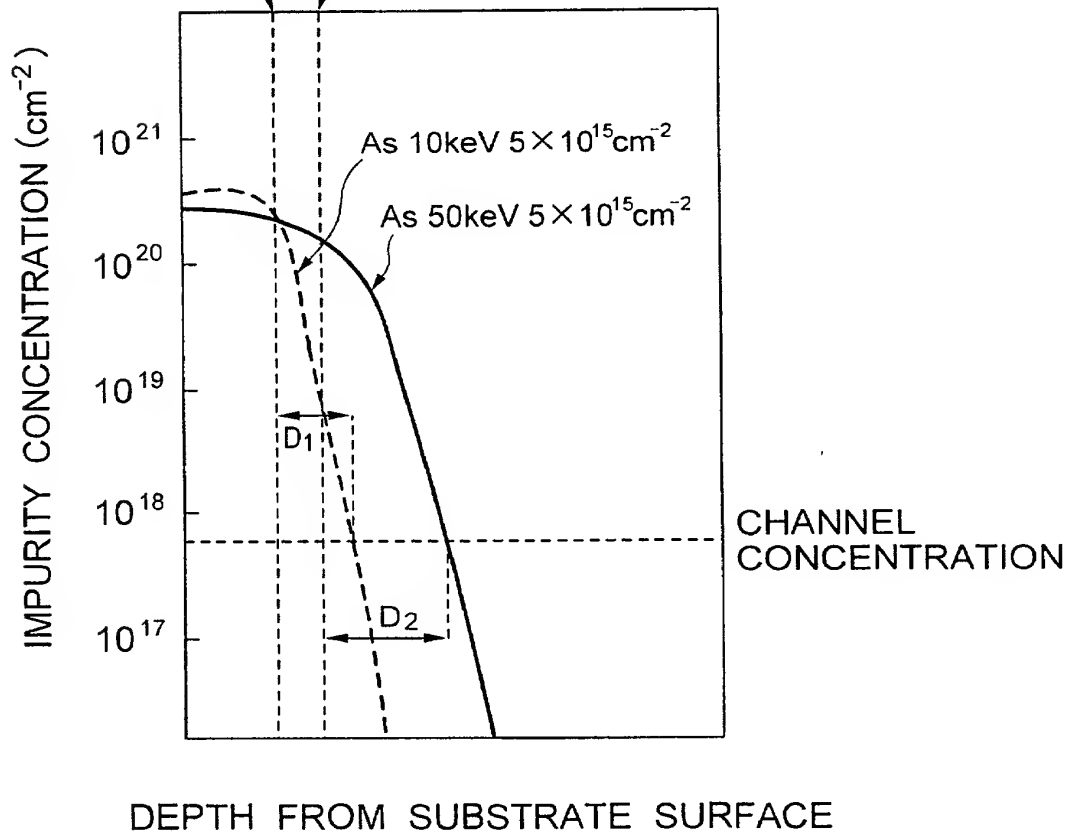


FIG. 6

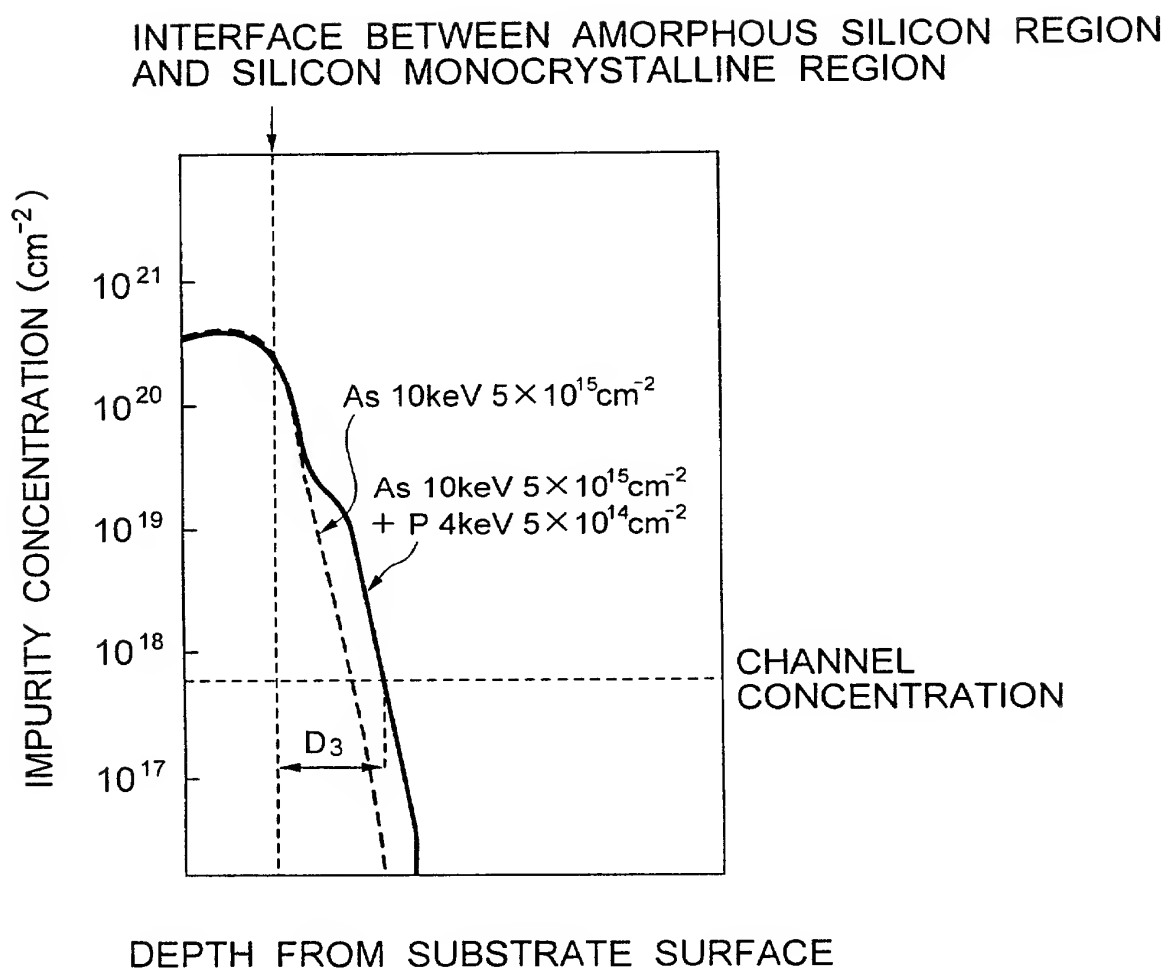


FIG. 7

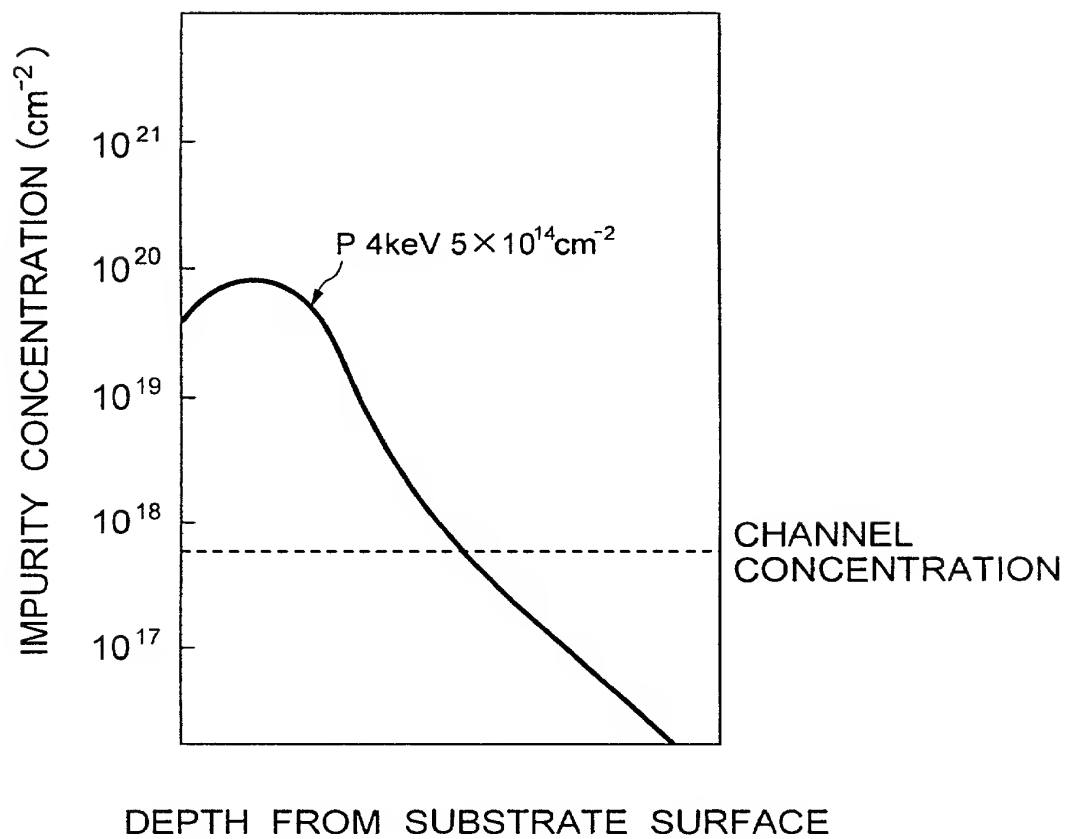


FIG. 8

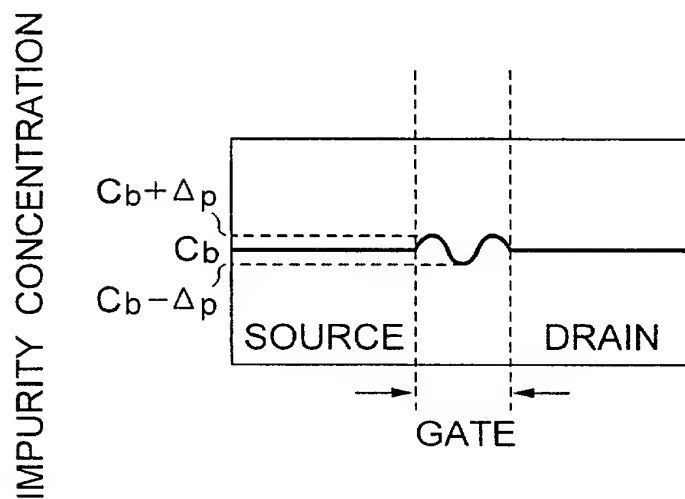


FIG.9

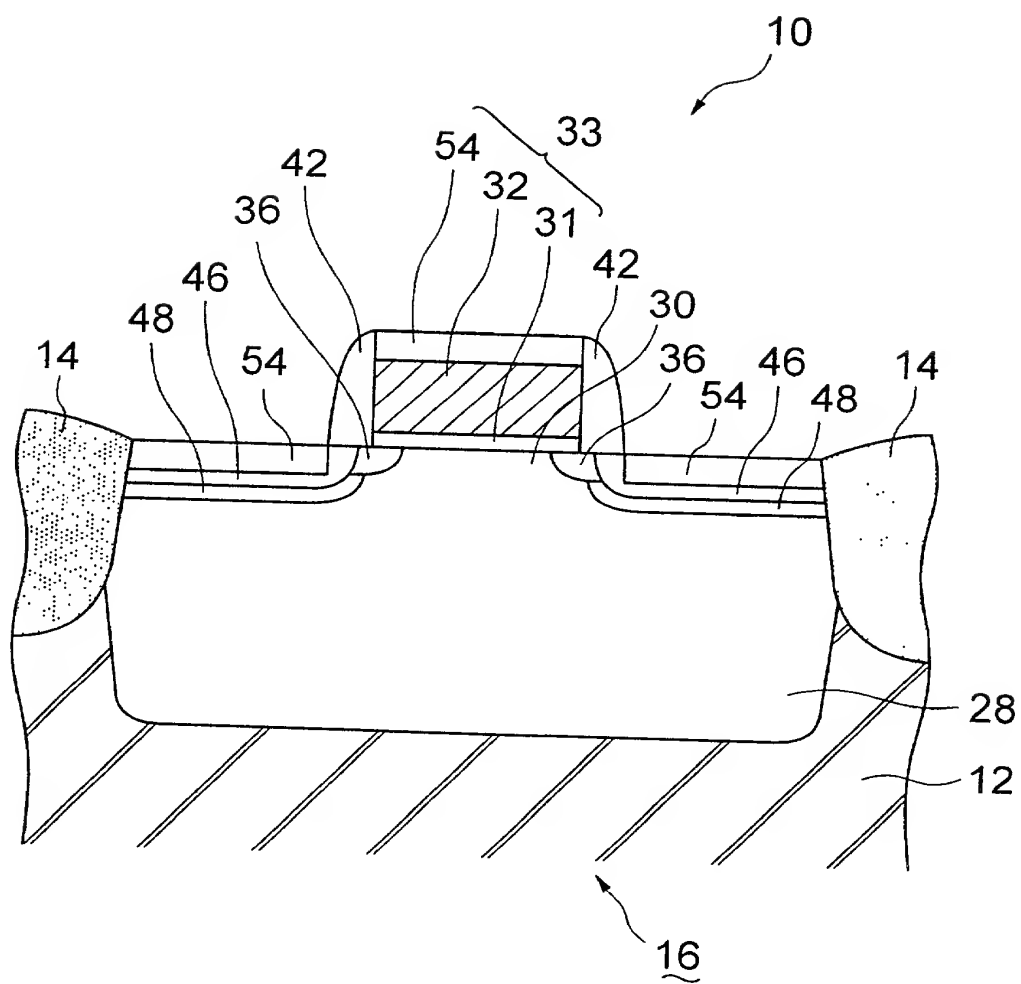


FIG.10A

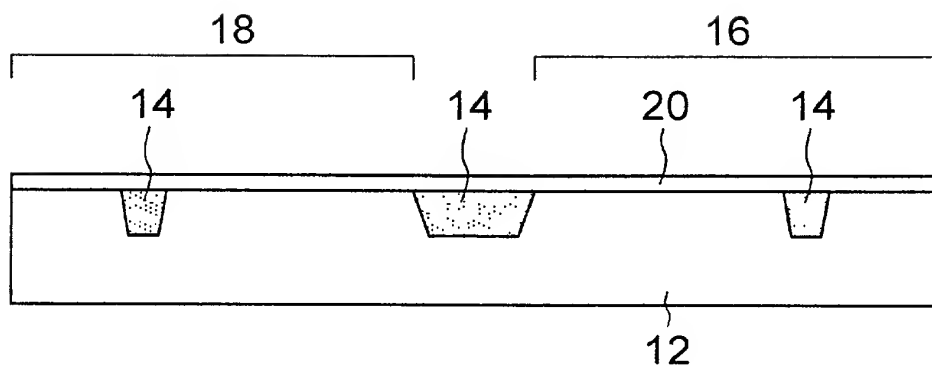


FIG.10B

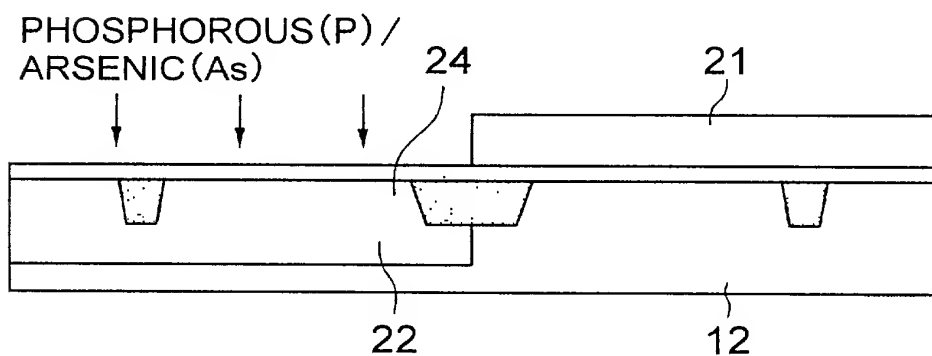


FIG.10C

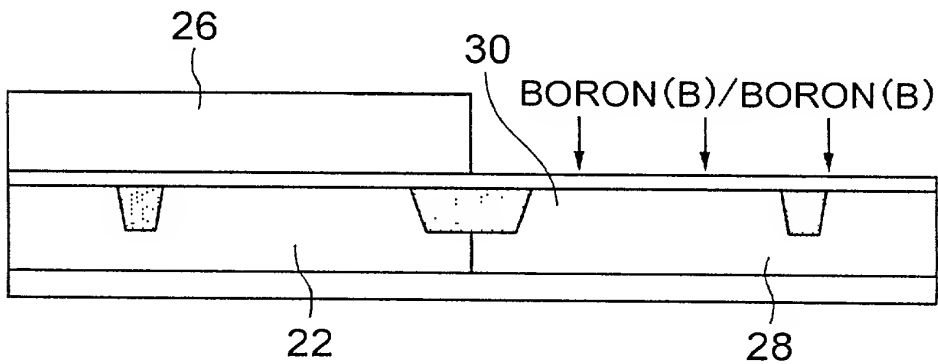


FIG.10D

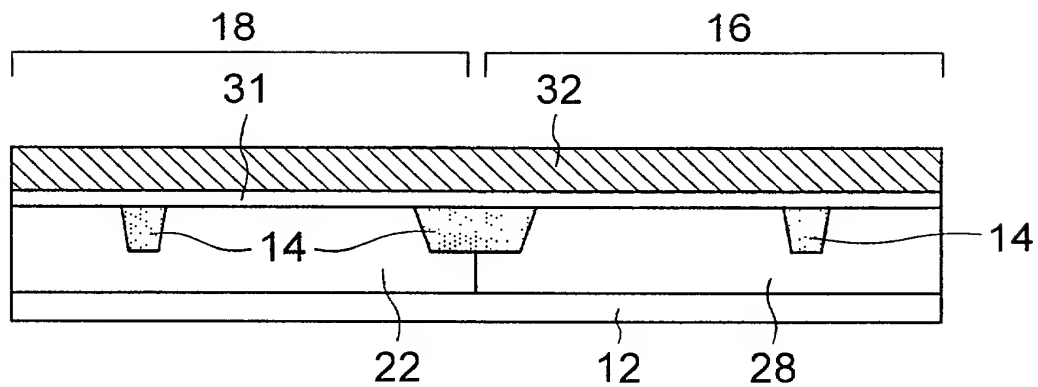


FIG.10E

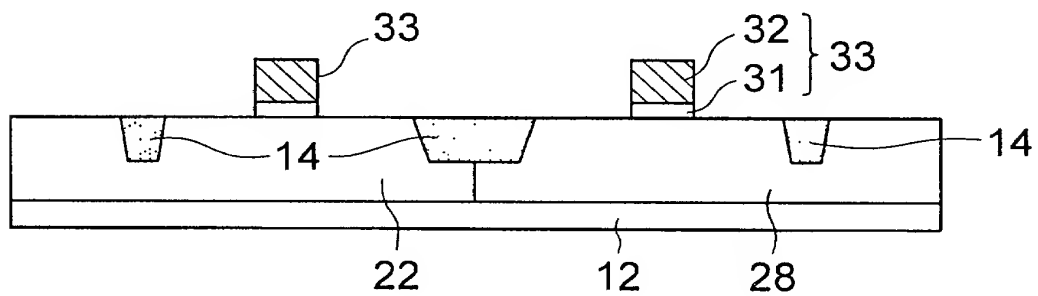


FIG.10F

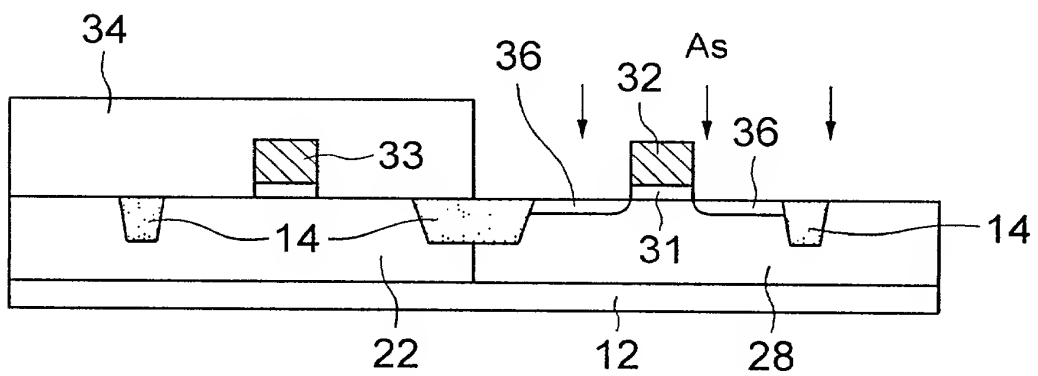


FIG.10G

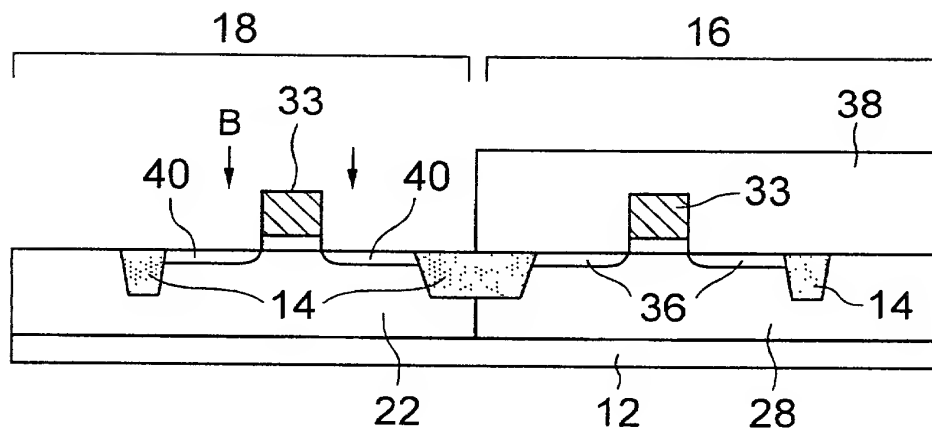


FIG.10H

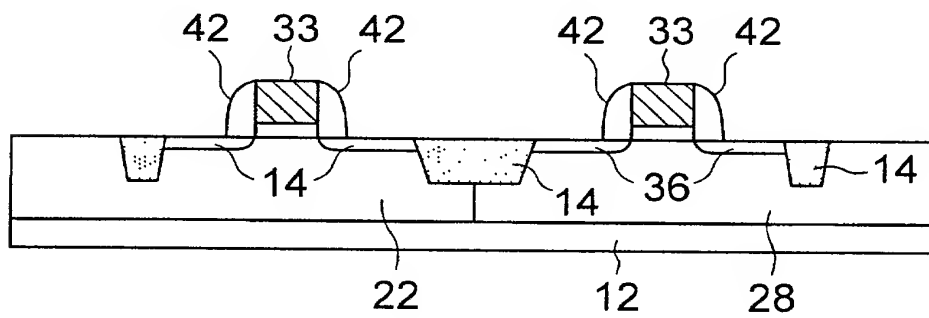


FIG.10 I

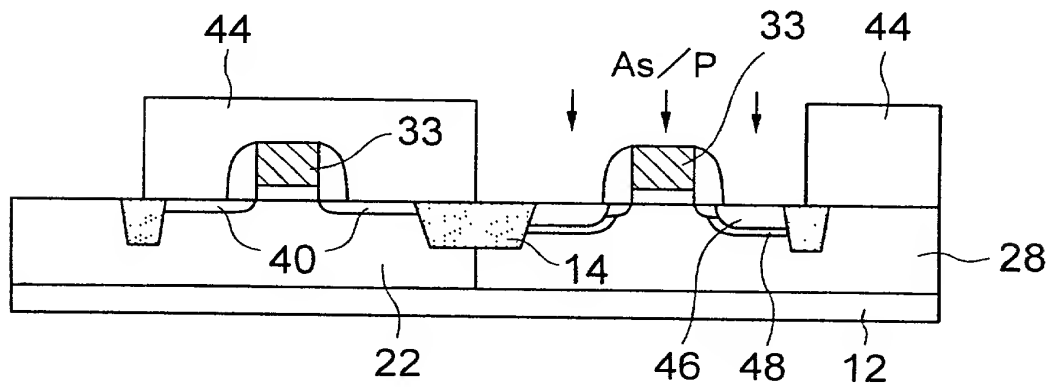


FIG.10J

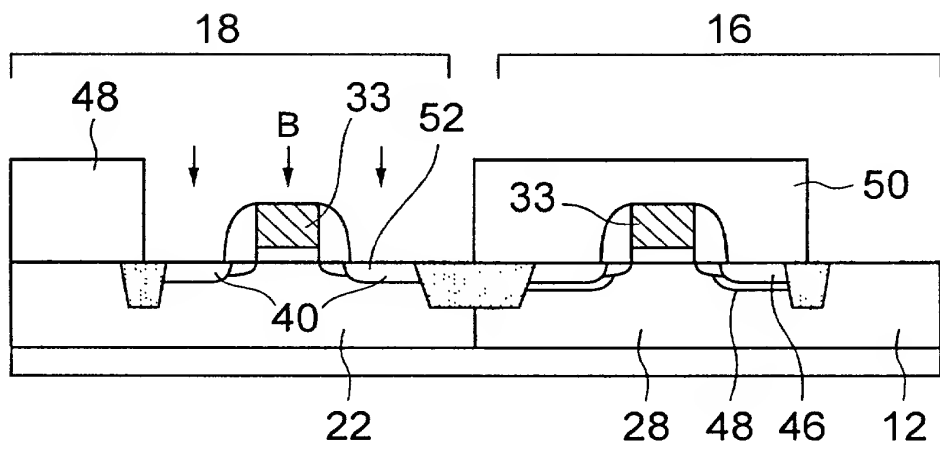


FIG.10K

